

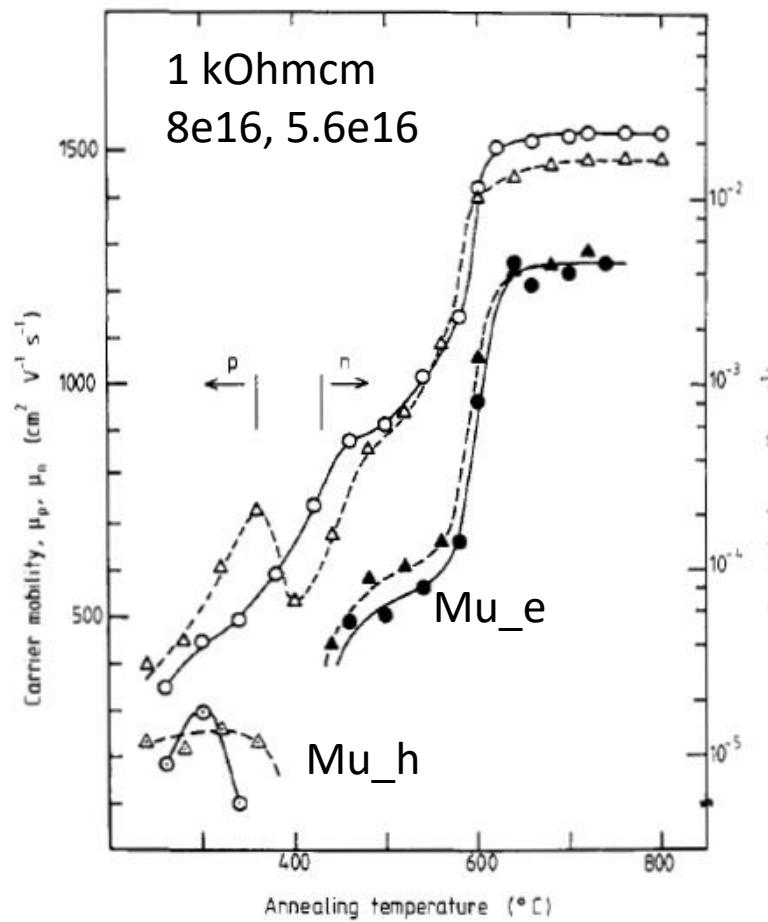
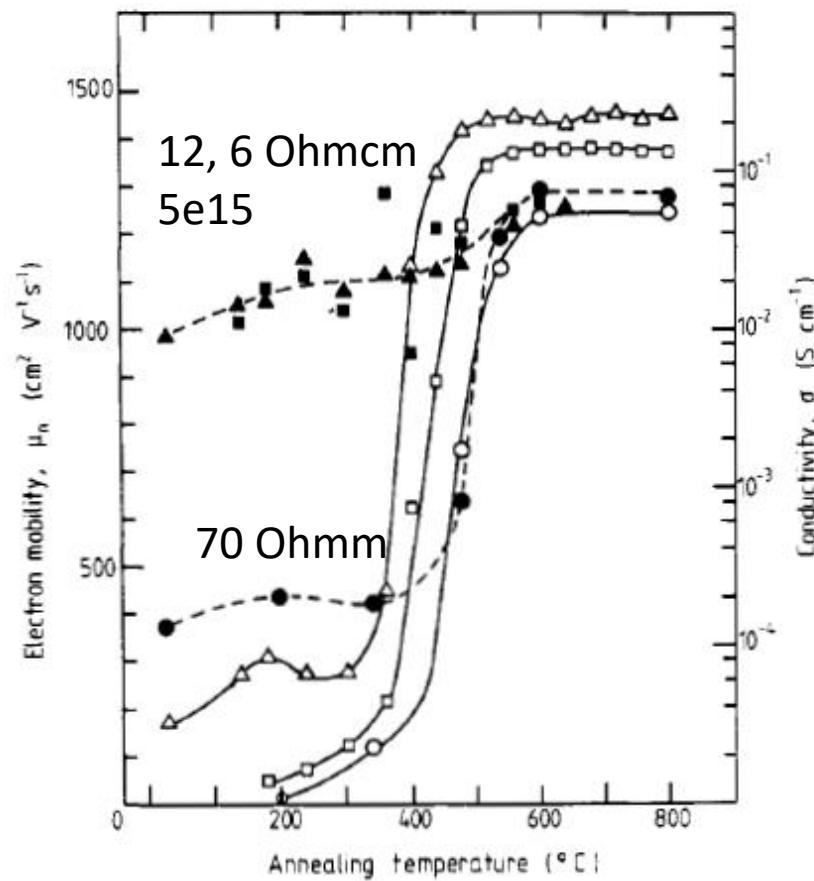
Pregled objav o vplivu obsevanja na gibljivost nosilcev

Sestanek SiC 24.4.2020

Nekaj objav iz obsevanj za neutron-transmutation. Pri tem jih je zanimalo, koliko od spremembe gibljivosti ostane po annealingu. Ni čisto jasno, kako so obsevali ... ampak vidi se očitna sprememba po obsevanju.
 Meritve s Hall efektom.

T Maekawa, S Inoue, M Aiura and A Usami, The effect of radiation damage on carrier mobility in neutron-transmutation-doped silicon Semicond. Sci. Technol. 3 (1988) 77-83.

Polni markerji mobility



HERMAN J. STEIN, Electrical Studies of Neutron-Irradiated n-Type Si: Defect Structure and Annealing,
Phys. Rev. Vol 163, No. 3, 1967

Meritve (Hall),
spremembe opazne tudi pri nizkih fluencah.

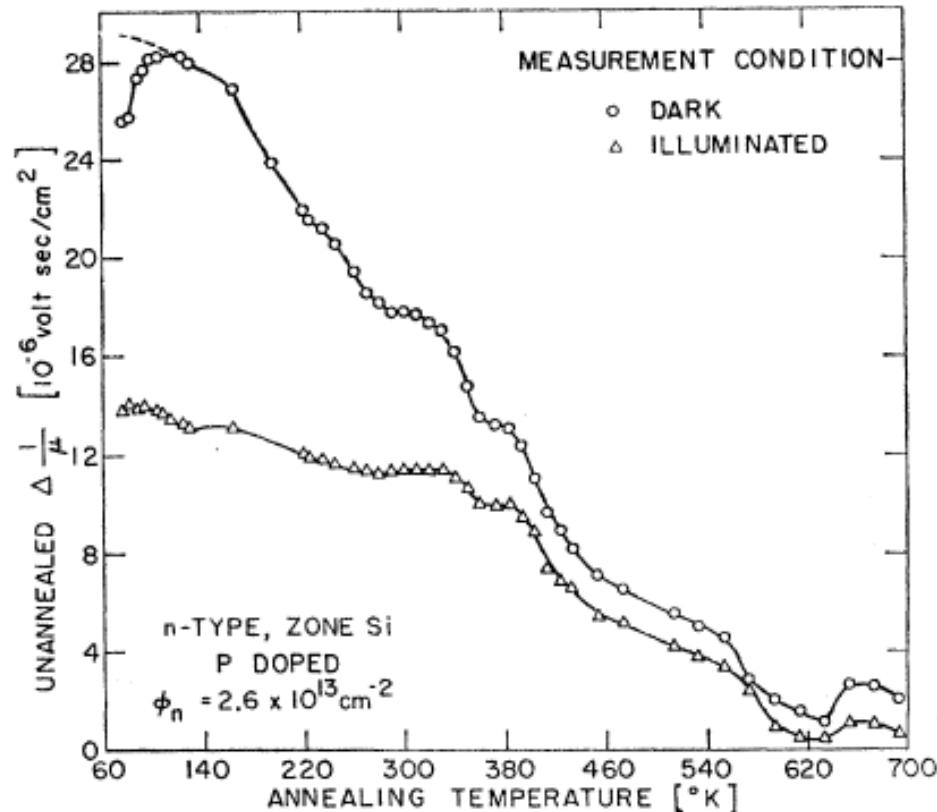


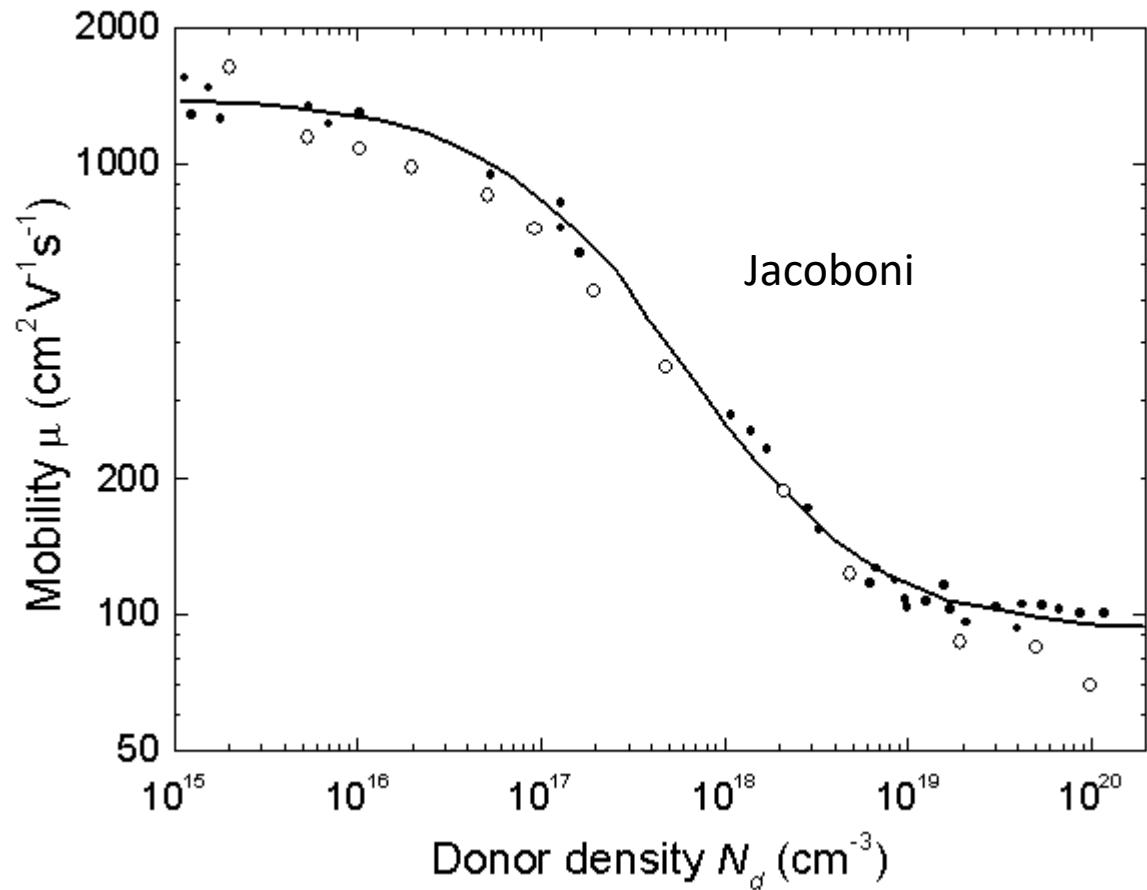
FIG. 8. Unannealed reciprocal mobility increase for float-zone silicon measured in the dark and under weak illumination at 76°K and plotted as a function of annealing temperature.

TCT meritve:

- 1) T.J. Brodbeck, A. Chilingarov, T. Sloan, E. Fretwurst, M. Kuhnke, G. Lindstroem (RD48)
Carrier mobilities in irradiated silicon, NIMA 477 (2002) 287–292
 - TCT meritve do 2.4×10^{14} n/cm² .. Ni sprememb gibljivosti (znotraj 10% natančnosti)
- 2) V. Eremin and Z. Li, Carrier drift mobility study in neutron irradiated high purity silicon, NIM A 362, 338 (1995),
[http://dx.doi.org/10.1016/0168-9002\(95\)00381-9](http://dx.doi.org/10.1016/0168-9002(95)00381-9)
 - TCT, do 5×10^{13} , ni opaznih sprememb

Veliko je člankov o vplivu sipanja na ioniziranih dopantih na gibljivost

- Electron drift mobility versus donor density, T=300 K. (Jacoboni et al. [1977]).
- Proceedings of the IEEE. 55 (12): 2192–2193. doi:10.1109/PROC.1967.6123.



Odvisnost od koncentracije N parametrizirajo s
(za N okrog 1e17):

$$\mu \sim \frac{\mu_0}{1 + \left(\frac{N}{N_{ref}}\right)^a}$$

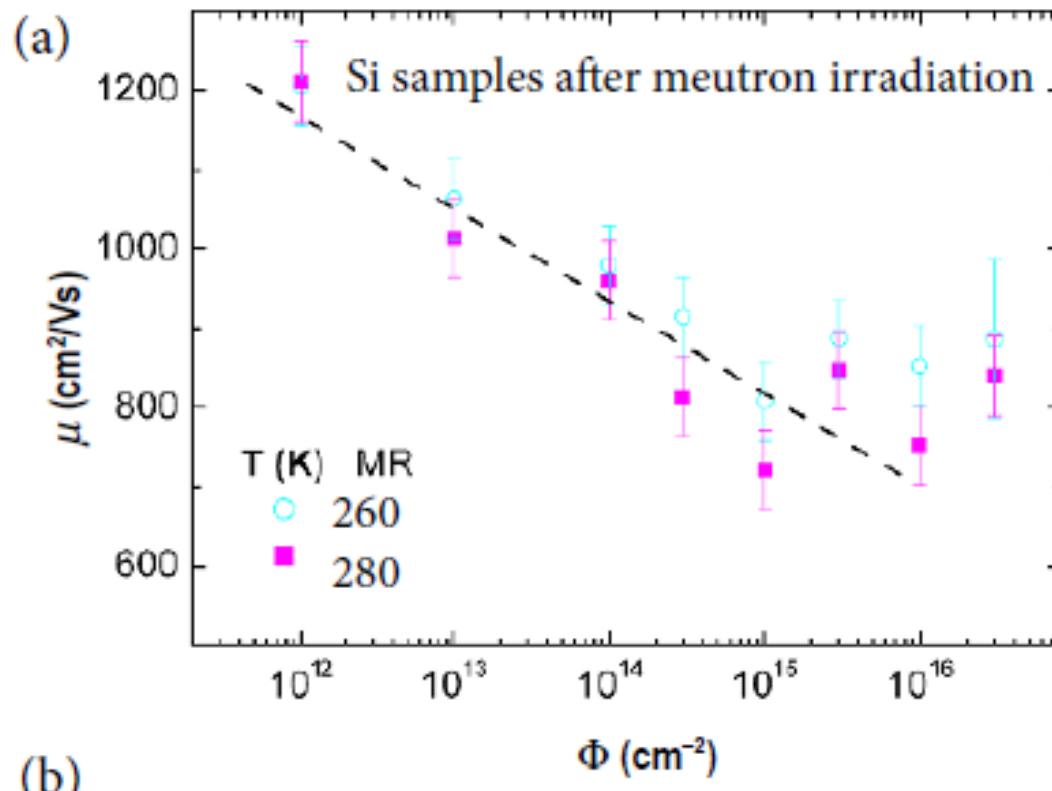
$$N_{ref} \sim 1E17 \text{ cm}^{-3}$$

$$a \sim 0.9$$

Novejše meritve

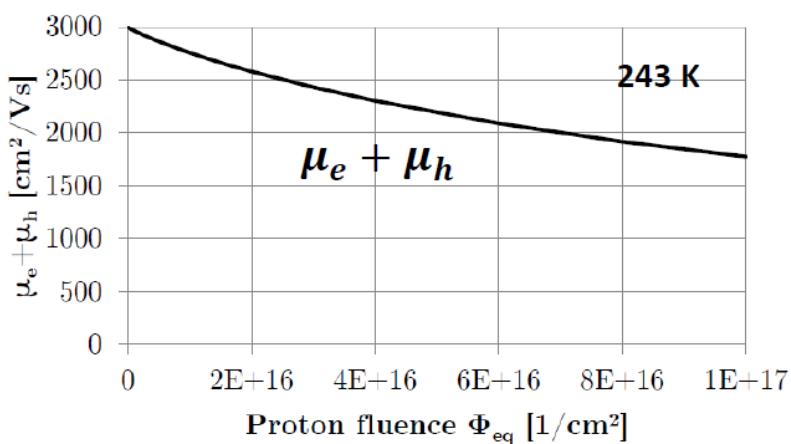
- J Vaitkus et al., NEUTRON IRRADIATION INFLUENCE ON MOBILITY AND COMPENSATION OF DARK CONDUCTIVITY IN SILICON, Lithuanian Journal of Physics, Vol. 56, No. 2, pp. 102–110 (2016)

Hall mobility:

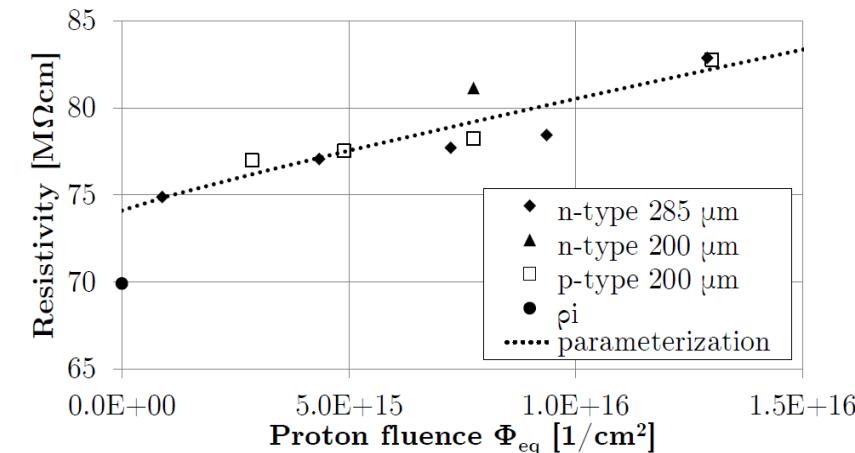


Meri Hallov efekt, ampak ni dobro napisano kako meri...

- Izmeri vsoto gibljivost iz meritev toka pri nizkih npetostih. Odvisnost od fluence (Beta_mob = 1.5e17 cm⁻²)
- Če vzame običajni scaling s koncentracijo ioniziranih nečistoč ($N_{\text{ref}} = 0.5\text{-}2.4 \cdot 10^{17} \text{ cm}^{-3}$) dobi iz svojega fita, da je g_{eff} za nabite defekte 1 cm⁻¹
- S tem dobi dosti manjši padec gibljivosti kot ga da E-TCT
- Naše številke bi dobili, če bi bil $g_{\text{eff}} \sim 10$



200 μm & 285 μm diodes
 $\rho = (en_i(\mu_e + \mu_h))^{-1}$



$$\rho_{\text{ohm}}(\Phi_{\text{eq}}) = 74.1 \text{ M}\Omega\text{cm} \cdot \left(1 + \left(\frac{\Phi_{\text{eq}}}{\beta_{\text{mob}}}\right)^{0.9}\right)$$

- Assume ionized impurity scattering dominates at 243 K

$$\mu(N) = \mu_{\min} + \frac{\mu_{\max} - \mu_{\min}}{1 + \left(\frac{N}{N_{\text{ref}}}\right)^{\varsigma}} \quad N_{\text{ref}} \approx (0.5 - 2.4) \cdot 10^{17} \text{ cm}^{-3}$$

Neglect $\mu_{\min} \rightarrow \mu_0^e(\Phi_{\text{eq}}) + \mu_0^h(\Phi_{\text{eq}}) \approx \frac{\mu_0^e + \mu_0^h}{1 + \left(\frac{\Phi_{\text{eq}}}{\beta_{\text{mob}}}\right)^{\varsigma}}$

$\beta_{\text{mob}} = 1.52 \cdot 10^{17} \text{ cm}^{-2}$
 $\beta_{\text{mob}} = N_{\text{ref}}/g_{\text{eff}}$
 $g_{\text{eff}} \approx 1 \text{ cm}^{-1}$